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Chemically Deposited PbSe Thin Films: Factors Deterring Reproducibility in the Early Stages of Growth

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Supplementary Information

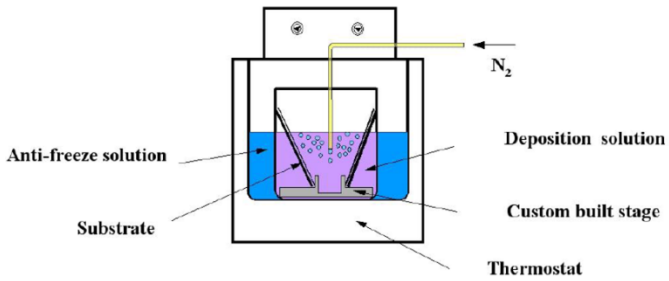

Figure S1. Schematic illustration of the chemical deposition reactor used in this work. Substrates are mounted epi-side down on a custom-designed Teflon stage at an angle of < 70° with respect to the air-solution interface. Adapted from Ref. 12.

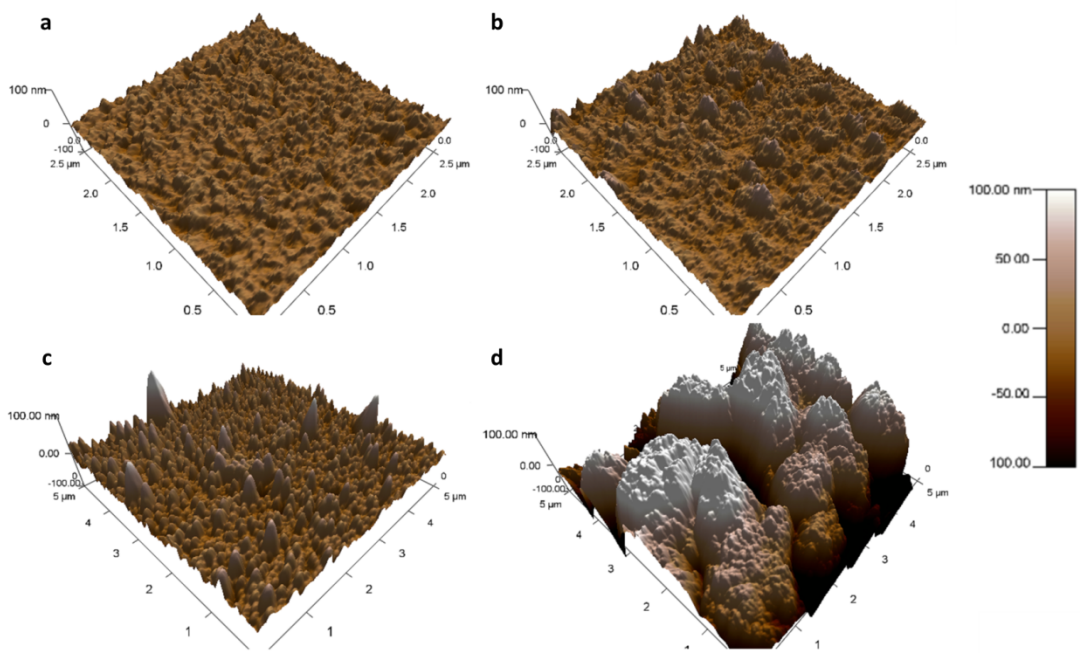

Figure S2. Scanning force imaging of PbSe films deposited at 20°C for 3 hours at varying hydroxide concentrations of (a) 0.3M (b) 0.6M (c) 1.2M (d) 2.4M. As can be observed, roughness and grain size increase with hydroxide concentration in solution.

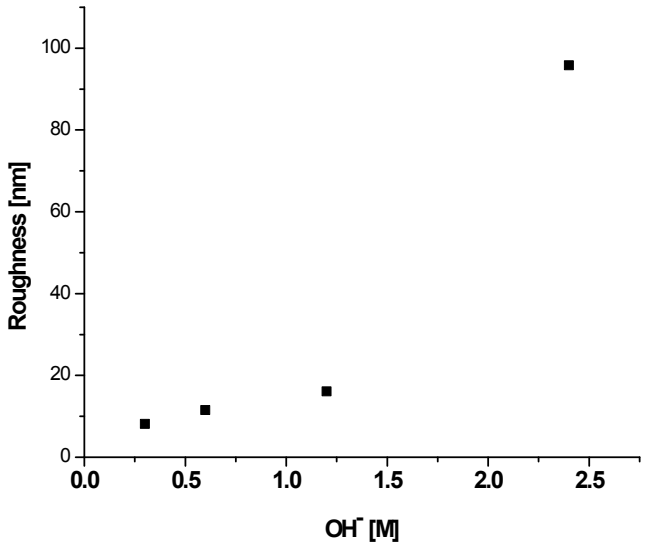

Figure S3. RMS roughness as a function of hydroxide concentration.